

JC979 U.S. PTO

10/038800



12/31/01

U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10038800	12/31/2001	430	313	1756	Datta Barreca

**APPLICANTS: Ma Ching-Tien; Chen Tsung-Chuan; Hsu Shew-Tsu;

**CONTINUING DATA VERIFIED: none

** FOREIGN APPLICATIONS VERIFIED: none

PG-PUB DO NOT PUBLISH ☐RESCIND ☐Foreign priority claimed ☐ yes ☒ no35 USC 119 conditions met ☐ yes ☒ no

Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

67,200-549

TITLE : Method for forming via and contact holes with deep UV photoresist

U.S. DEPT. OF COMM./PAT. & TM.-PTO-435L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
Assistant Examiner		DRAWING	
		Sheets Drwg.	Print Fig.
Amount Due		Application Examiner	
Date Paid			
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	
		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.	

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